



<b>Session Title:</b>	<b>[TuD2] Advanced Lithography II</b>
<b>Session Date:</b>	<b>November 12 (Tue.), 2024</b>
<b>Session Time:</b>	<b>15:00-16:30</b>
<b>Session Room:</b>	<b>Room D (Sidney Room, 2F, Paradise Hotel Busan)</b>
<b>Session Chair:</b>	<b>Prof. Sangsul Lee (POSTECH, Korea)</b>

[TuD2-1] [Invited]

15:00-15:30

TEL's Challenge for High NA EUV

Kyoungho Jang (TEL, Korea)

[TuD2-2] [Invited]

15:30-16:00

High NA EUV Lithography: Prospects and Challenges

Seo-Min Kim (SK hynix Inc., Korea)

[TuD2-3] [Invited]

16:00-16:30

High NA EUV: What does it change for Design, OPC and Mask?

Youssef Drissi, Yasser Sherazi, Victor Blanco, Kenichi Miyaguchi, Werner Gillijns, and Ryan Ryoung Han Kim (imec, Belgium)